

Resistance and surface potential characterization of 2-d materials with atomic force microscopy

Nicolas F. Martinez and Louis Pacheco

Concept Scientific Instruments,
1 Terre de Feu 91940 Les Ulis France

f.martinez@csinstruments.eu

Over the past 30 years, Atomic Force Microscopy has evolved from a microscope to measure just the surface topography to a wide variety of measurement modes that provides a way to characterize other atomic interactions or physical properties like magnetic field, electric field, nanoscale dissipation processes, thermal conductivity, electrical conductivity, resistance, surface potential, piezoresponse, Young modulus,... Electrical nanocharacterization with AFM has emerged as a powerful tool to map electrical properties at the nanoscale, like surface potential (work function) and conductivity. However, traditional setups in AFM make difficult to obtain accurate and repeatable results over several types of samples.

In this contribution we will show the capabilities new developed AFM modes: High Definition Kelvin Force Microscopy (HD-KFM), ResiScope, Soft-Resiscope and Scanning Microwave that overcome the intrinsic difficulties of electrical nanocharacterization with AFM. This techniques have been applied on a variety of samples of 2-D materials providing high stability, sensitivity and lateral resolution

References

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Figures

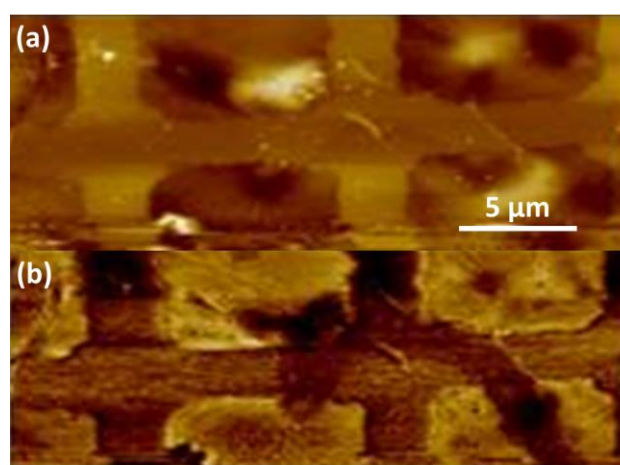


Figure 1: Topography (a) and surface potential (b) of a graphene membrane suspended over a grid of Si/SiO₂.